

Chemicals supplied to NRF Users

Acids

Sulfuric Acid - H ₂ SO ₄	chrome etch 1020
BOE 6:1 – NH ₄ F/HF	Aluminum etch
Hydrochloric acid - HCL	iron oxide mask etch
Phosphoric acid – H ₃ PO ₄	chrome mask etch
Hydrofluoric acid - HF	Freckle Etch
Nitric acid – HNO ₃	Iron Oxide Mask Etch
gold etch	

Bases

Ammonium hydroxide – NH ₄ OH
Hydrogen Peroxide – H ₂ O ₂

General Solvents

Propanol (Isopropanol)(2-propanol)
Methanol
Acetone

Photolithography

AZ1512
AZ9260
AZ nLOF 2035
Microchem LOR-A
Microchem 950PMMA A2
Microchem 950PMMA A4
Microchem 950PMMA A6
MIBK/IPA (1:3)
PRS 3000
NMP (AZ NMP Rinse)

Special Notes about chemicals:

- Small quantities for pipette dispensing the following photochemicals may be found in the Litho Bay rack, lower shelf.
 - **Shibley Microposit S1813**
 - **AZ 9260**
 - nLOF 2035
 - LOR3A
- PMMA is located in the Ebeam Bay solvent bench, lower right door.